

MAGNETRON SPUTTERING

Brand-Model

MSS LAB350, MAGNETRON SPUTTERING

Descriptions

Pumping system; Rotary pump (WSA W2V20, 200 L/min, Dual stage, 220V), Turbo pump: Leybold Turbovac 350i, 350 L/min, 10A/24V), System pressure (xE-5 Torr within 30 minutes). Generally, cooling at outer side, Mounting on ISO 200-K flange.

Specifications

Stage size: Up to 4" diameter
Rotation: Variable up to 20rpm
Heating: MoSi Heating Element
Heating range: 150°C-800°C
Bias capability: RF Bias to 30W
Thickness monitor: Inficon SQM-160. Quartz Crystal Sensor
Process Gas: Ar, O₂, N₂/MFC Unit

Service location

03-01-09 *Thin Film Laboratory*
Block: T05

Further Information

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Operator

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- Tel : -
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Notes:



CHAMBER